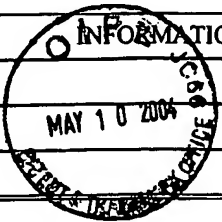


U.S. Department of Commerce, Patent and Trademark Office		Atty Docket No.	Serial No.
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		Applicant(s)	
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		Filing Date	Group
		March 23, 2004	Unassigned

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PN	A	2,759,106	8/14/56	Hans Wolter	250	53	
	B	3,150,483	5/10/62	Mayfield, et al.	60	35.5	
	C	3,232,046	2/1/66	Rudolf Meyer	50	35.5	
	D	3,279,176	10/18/66	Robert H. Boden	60	202	
	E	3,746,870	7/17/73	Donald M. Demarest	250	227	
	F	3,960,473	6/1/76	Thomas Harris	425	467	
	G	3,961,197	6/1/76	John M. Dawson	250	493	
	H	3,969,628	7/13/76	Roberts, et al.	250	402	
	I	4,042,848	8/16/77	Ja Hyun Lee	313	231.6	
	J	4,088,966	5/9/78	Michael A. Samis	313	231.5	
	K	4,143,275	3/6/79	Mallozzi, et al.	250	503	
	L	4,162,160	7/24/79	Gerald J. Witter	75	246	
	M	4,203,393	5/20/80	Dante S. Giardini	123	30	
	N	4,504,964	3/12/85	Cartz, et al.	378	119	
	O	4,536,884	8/20/85	Weiss, et al.	378	119	
	P	4,538,291	8/27/85	Seiichi Iwamatsu	378	119	
	Q	4,596,030	6/17/86	Herziger, et al.	378	119	
	R	4,618,971	10/21/86	Weiss, et al.	378	34	
	S	4,626,193	12/2/86	Ronald A. Gann	431	71	
	T	4,633,492	12/30/86	Weiss, et al.	378	119	
	U	4,635,282	1/6/87	Okada, et al.	378	34	

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	X	4,837,794	6/6/89	Riordan, et al.	378	119	
	Y	5,023,897	6/11/91	Neff, et al.	378	122	
	Z	5,027,076	6/25/91	Horsley, et al.	324	674	
	AA	5,102,776	4/7/92	Hammer et al.	430	311	
	BB	5,126,638	6/30/92	Rolf Dethlefsen	315	326	
	CC	5,142,166	8/25/92	Daniel L. Birx	307	419	
	CC	5,313,481	5/17/94	Cook et al.	372	37	
	DD	5,411,224	5/2/95	Dearman, et al.	244	53	
	EE	5,448,580	9/5/95	Birx et al.	372	38	
	FF	5,504,795	4/2/96	Malcolm McGeoch	378	119	
	GG	5,729,562	3/17/98	Birx et al.	372	38	
	HH	5,763,930	6/9/98	William N. Partlo	250	504	
	II	5,866,871	2/2/99	Daniel L. Birx	219	121	
	JJ	5,936,988	8/10/99	Partlo et al.	372	38	
	KK	5,963,616	10/5/99	Silfvast, et al.	378	122	
	LL	6,031,241	2/29/00	Silfvast, et al.	250	504	
	MM	6,039,850	3/21/00	Stephen C. Schulz	204	192.15	
	NN	6,172,324	1/9/01	Daniel L. Birx	219	121.57	

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	PP	6,064,072	5/16/00	Partlo, et al.	250	504	
	QQ	6,195,272	2/27/01	Joseph E. Pascente	363	21	
	RR	6,452,199	9/7/02	Partlo, et al.	250	504	
	SS	6,466,365	10/15/02	Maier, et al.			
	TT	6,496,528	12/17/02	Titus, et al.			
	UU	6,566,667	5/20/03	Partlo, et al.	250	504	
	VV	6,566,668	5/20/03	Rauch, et al.	250	504	
	WW	6,576,912	6/10/03	Visser, et al.	250	492.2	
	XX	6,586,757	7/1/03	Melnychuk, et al.	250	504	
	AA	10/608,521	6/26/03	Rafac, et al.			
	AB	2001/0055364	12/27/01	Kandaka, et al.	378	119	
	AC	2002/0100882	8/1/02	Partlo, et al.	250	504	
	AD	2002/0163313	1/9/03	Ness, et al.	315	111.01	
	AE	2002/0168049	11/14/02	Schriever, et al.	378	119	
	AF	2003/0006383	1/9/03	Melnychuk, et al.	250	504	
	AG	2003/0068012	4/10/03	Ahmad, et al	378	119	
	AH	2003/0219056	11/27/03	Yager, et al.	372	57	

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PN	AJ	Apruzese, J.P., "X-Ray Laser Research Using Z Pinches," <u>Am. Inst. of Phys.</u> 399-403, (1994).						
	AK	Bollanti, et al., "Compact Three Electrodes Excimer Laser IANUS for a POPA Optical System," <u>SPIE Proc.</u> (2206)144-153. (1994).						
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	AW	Lee, Ja H., "Production of dense plasmas in hypocylindrical pinch apparatus," <u>The Phys. Of Fluids</u> , 20(2):313-321 (1977).						
	AX	Lewis, Ciaran L.S., "Status of Collision-Pumped X-ray Lasers," <u>Am Inst. Phys.</u> Pp. 9-16 (1994).						
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PN	BA	Mayo, et al., "A magnetized coaxial source facility for the generation of energetic plasma flows," <u>Sci. Technol.</u> Vol. 4:nn.47-55 (1994).						
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	BD	Partlo, et al., "EUV (13.5nm) Light Generation Using a Dense Plasma Focus Device," <u>SPIE Proc. On Emerging Lithographic Technologies III</u> , Vol. 3676, 846-858 (March 1999).						
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	BG	Qi, et al., "Fluorescence in Mg IX emission at 48.340 Å from Mg pinch plasmas photopumped by Al XI line radiation at 48.338 Å," <u>The Am. Phys. Soc.</u> , 47(3):2253-2263 (March 1993).						
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	BK	Silfvast, et al., "High-power plasma discharge source at 13.5 nm and 11.4 nm for EUV lithography," <u>SPIE</u> , Vol. 3676:272-275, (Mar. 1999).						
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	BM	Wilhein, et al., "A slit grating spectrograph for quantitative soft x-ray spectroscopy," <u>Am. Inst. Of Phys. Rev. of Sci. Instrum.</u> , 70(3):1694-1699. (Mar. 1999).						
	BN	Wu, et al., "The vacuum Spark and Spherical Pinch X-ray/EUV Point Sources," <u>SPIE, Conf. On Emerging Tech. III Santa Clara CA Vol 3676-410-420 (Mar 1999)</u>						
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